Evaluation of emittance measurements data consistency – PITZ-PoV

L. Staykov
Mini Workshop on
"Characterization of High Brightness Beams"

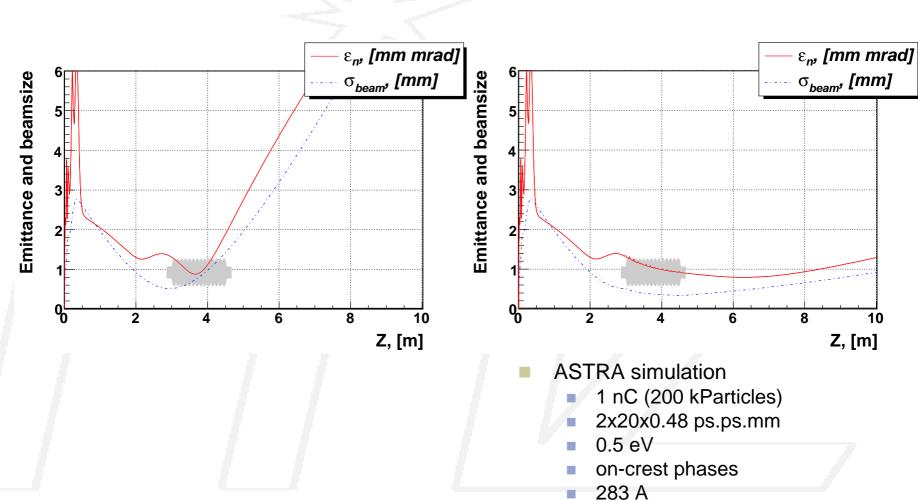
Zeuthen, May 27th, 2008

Featuring

- Motivation
- Emittance measurements at PITZ
 - method
- Criteria for data consistency
 - PPoV

Discussions

Injector topology



22 MeV

0.76 mm.mrad

Emittance measurement

Single slit mask method

single slit method:

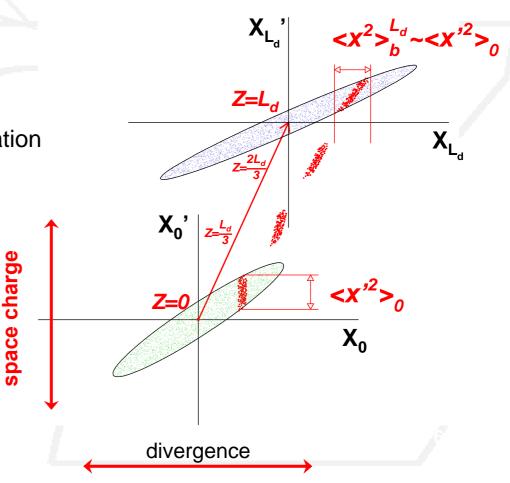
direct measurement "multi-shot" accumulates jitter sheared divergence approximation

$$\mathcal{E}_{x,n} = \beta \gamma \cdot \sqrt{\langle x^2 \rangle \cdot \langle x'^2 \rangle}$$

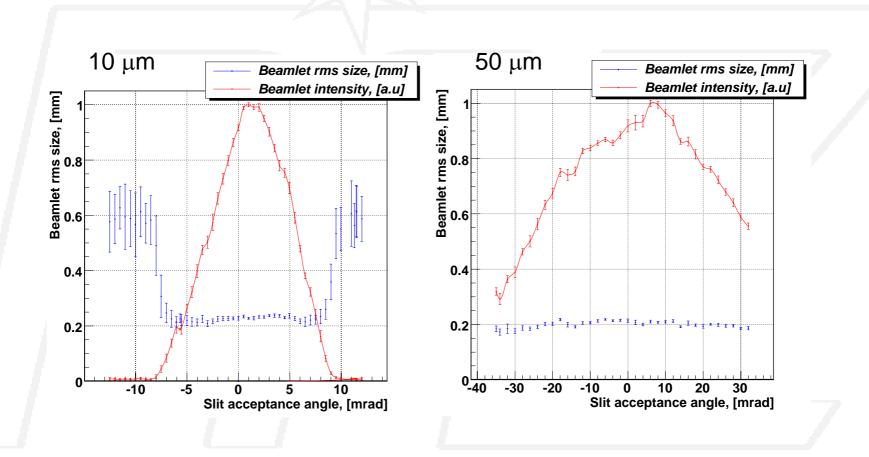
$$\left\langle x_{i}^{2}\right\rangle = \sqrt{\frac{\left\langle x_{b}^{2}\right\rangle_{i}}{L_{d}^{2}}}$$

local divergence

$$\langle x'^2 \rangle = \frac{1}{n} \cdot \sum_{i=1}^n w_i \cdot \langle x'_i^2 \rangle$$



Reply from yesterday slit scattering effects



Criteria

- Machine setup and monitoring
- Completeness of data
- Quality of data
 - S_2N
 - instruments
 - amplitude range
 - optical resolution
 - method specifics
 - jitter
- Data treatment

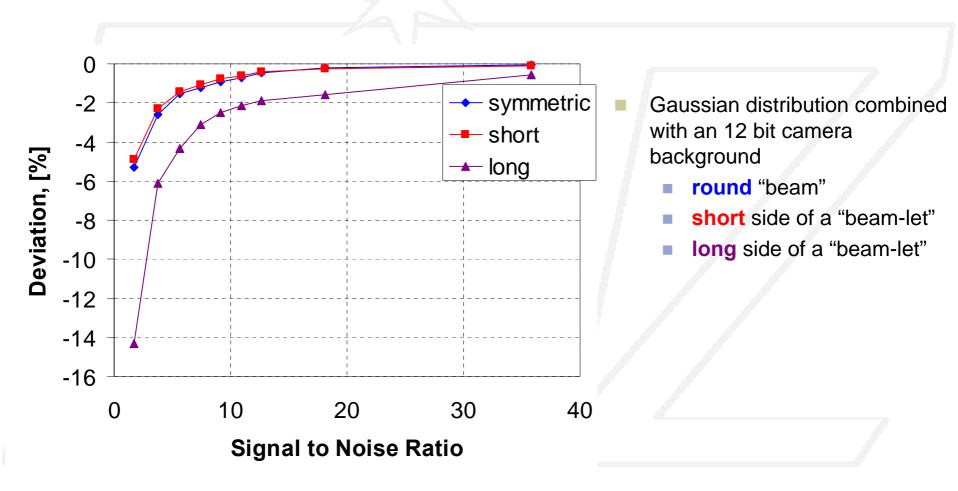
Machine setup and monitoring

- Establishment and control of the main parameters
 - bunch charge
 - RF phases and amplitudes
 - beam momentum and momentum distribution
 - beam trajectory
 - **...**
- Fast and reliable procedures

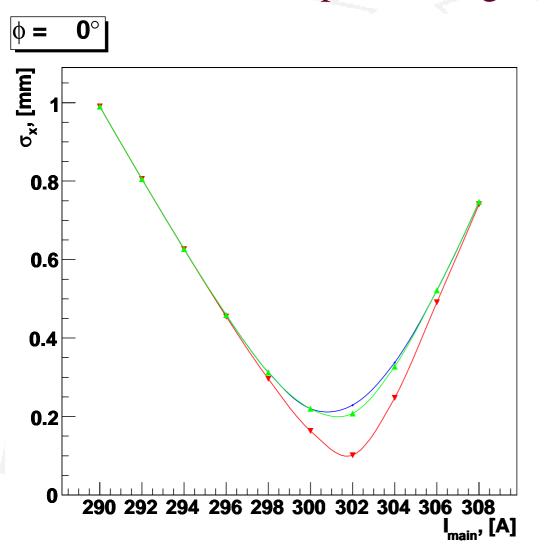
Completeness of data

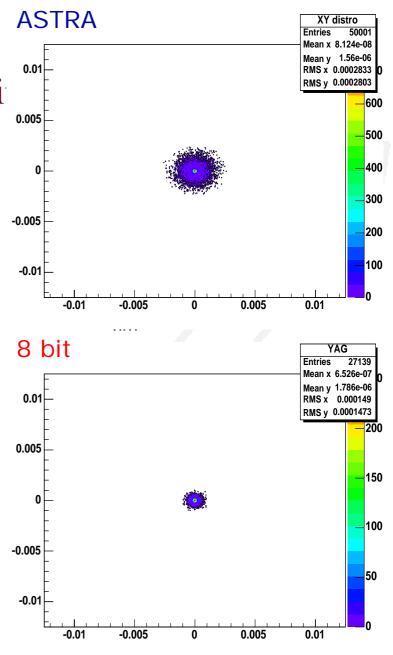
- Beam and beam-let sizes ©
 - mean momentum and momentum distribution <u>at each possible</u>
 <u>location</u> (i.e. after gun, etc.)
 - statistical overview
- Auxiliary data
 - phase scans
 - charge vs. gun phase (hints on longitudinal laser distro, gradient@cathode etc.)
 - momentum vs. RF phases (hint on the field distribution)
 - beam size vs. Z
 - lattice PS currents
 - cathode laser monitoring
 - Q.E.
 - etc...
- Automation solves most problems
- Data statistics

3x sigmask @ Signal to Noise Ratio



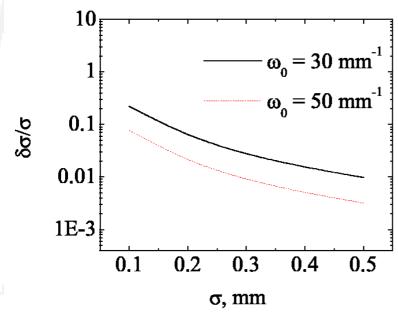
instruments – amplitude range (bi



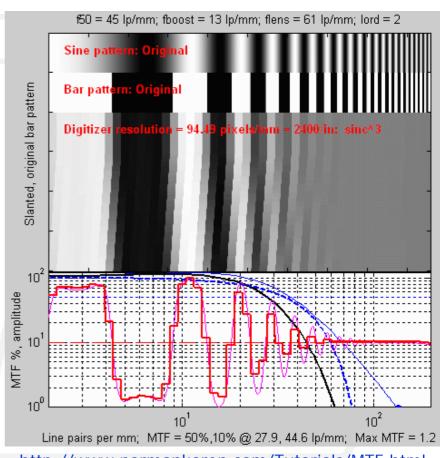


instruments – optical contribution

- MTF formalism used
- Uncertainty as a function of beam size



TRANSVERSE BEAMSIZE MEASUREMENT SYSTEMS AT PITZ R. Spesyvtsev, diploma thesis



http://www.normankoren.com/Tutorials/MTF.html

Quality controlinstruments - method specifics

- Envelope equations for nonsymmetric beam
 - Used to calculate the beamlet evolution
 - Estimates the influence of the slit opening due to space charge on the beamlet size
- Uniform distribution used to solve the system

General parameters:

$$I_{\rm p} = 50, A$$

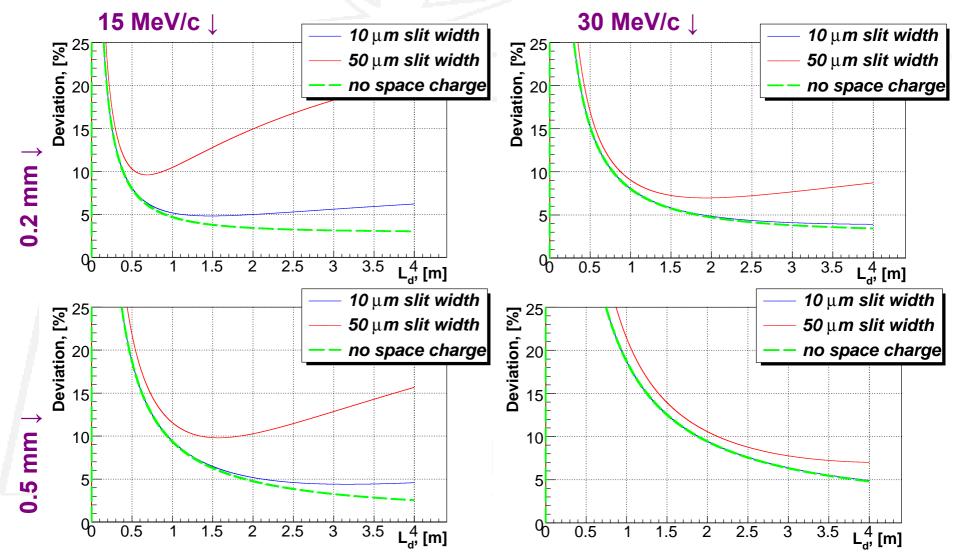
$$= \gamma = 10..60$$

$$\sigma_{x} = 0.2.2$$
, mm

$$\sigma'_{x}$$
 - scaled such that

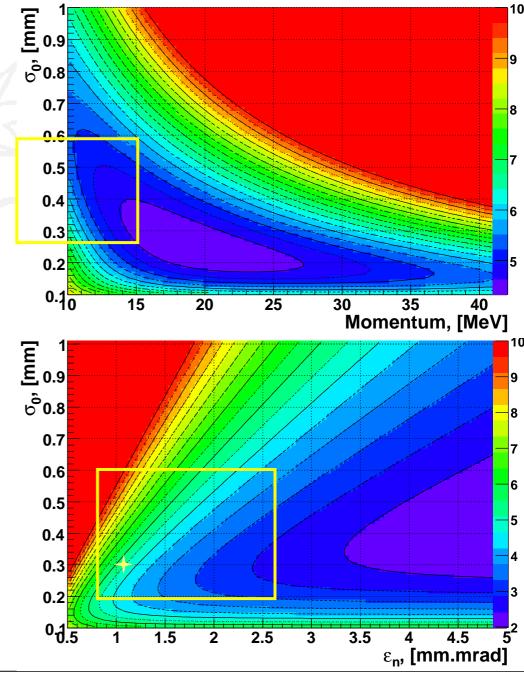
$$\epsilon_{x} = 0.9 \text{ mm.mrad}$$

instruments – method specifics



Quality control method specifics

- Single slit method uncertainties
 - as a function of beam momentum and the initial rms size, ε_n=0.9 (upper plot)
 - as a function of the initial rms size and the emittance
 - mean momentum
 - 15 MeV/c
 - 30 MeV/c
 - slit opening 10 μm
 - $L_d = 2 m$
 - optic resolution 50 l/mm



Miscellaneous

- Jitter
 - discussions in talk of MK
- Data treatment variations
 - sigmask
 - fit methods
 - rms methods
 - "cut" methods

Conclusions

- Data consistency is affected by numerous factors
 - machine setup and performance
 - data ensemble
 - data treatment
- Higher attention needed during the preparation and execution of emittance measurements
- Automation solve most of the problems
 - but new emerge

Discussions



The END

- STOP!
 - don't click further!!!